

IN THE CLAIMS:

Please cancel claims 6, 7, 14, 16 to 25 without prejudice and amend the claims as follows.

1. (currently amended) An article comprising a body made of quartz glass having improved corrosion resistance against plasma, ~~the quartz glass being doped with a metallic element~~, the quartz glass containing bubbles and crystalline phase at a quantity accounting for less than 100 mm<sup>2</sup> in a projection area per 100 cm<sup>3</sup> of the quartz glass body, and said quartz glass body having a metallic element containing surface layer having a thickness of at least 5 mm containing 0.1 to 20 % by weight of a metallic element, wherein the metallic element is selected from the group consisting of Sm, Y, Zr and Ti.
2. (original) An article as claimed in Claim 1, wherein the metallic element has a boiling point higher than that of a Si fluoride.
3. (previously amended) An article as claimed in Claim 1, wherein the metallic element is able to react with fluorine to form a fluoride compound and the fluoride compound of said metallic element having a boiling point that is higher than that of the fluoride compound of Si (SiF<sub>4</sub>).
4. (currently amended) An article as claimed in Claim 1, wherein the metallic element further comprises a second element is one or two elements selected from the group consisting of Sm, Eu, Yb, Pm, Pr, Nd, Ce, Tb, Gd, Ba, Mg, Y, Tm, Dy, Ho, Er, Cd, Co, Cr, Cs, Zr, Al, In, Cu, Fe, Bi, Ga, and Ti.
5. An article as claimed in Claim 1, wherein said metallic element is present in a concentration in a range of from 0.1 to 20 % by weight.
6. (canceled)
7. (canceled)
8. An article as claimed in Claim 6, wherein the metallic element is additionally applied to a surface thereof.

9. An article as claimed in Claim 1, said quartz glass body having a surface roughness Ra of 0.01 to 10  $\mu\text{m}$ .
10. An article as claimed in Claim 9, wherein said body has a surface that is brought into contact with a plasma corrosive gas, said surface being obtained by subjecting the surface to a precision cutting treatment, or a heating and melting treatment, ~~or-a heating and melting treatment followed by a chemical etching treatment.~~
11. An article as claimed in Claim 1, wherein the quartz glass has an OH concentration of 100 to 2000 ppm.
12. An article as claimed in Claim 1, wherein 2 mol/m<sup>3</sup> or less of a gas is discharged from the article when it is heated are generated in a temperature range of from room temperature to 1000 °C.
13. An article as claimed in Claim 1, wherein the quartz glass has an internal transmittance for a visible radiation of 50 %/cm or higher.
14. (canceled).
15. An article as claimed in Claim 1, wherein the body is configured to function as a jig for supporting wafers.

Claims 16 to 25 (canceled).

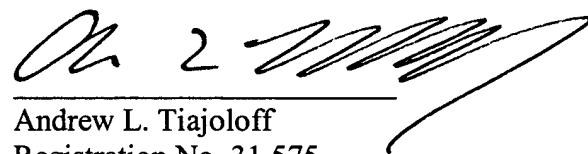
26. (new) An article as claimed in Claim 10, wherein said surface is subjected to said heating and melting treatment followed by a chemical etching treatment.

**REMARKS**

Applicant here elects Group I, and also amends the claims to better express the invention being claimed.

Should any questions arise, the Patent Office is invited to telephone attorney for applicant at 212-490-3285.

Respectfully submitted,



Andrew L. Tiajoloff  
Registration No. 31,575

Tiajoloff & Kelly  
Chrysler Building, 37<sup>th</sup> floor  
405 Lexington Avenue  
New York, NY 10174

tel. 212-490-3285  
fax 212-490-3295